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First Named Inventor	Kirk D. Prall
Serial No.	10/738,408
Filing Date	December 16, 2003
Group Art Unit	2818
Examiner Name	Unknown
Confirmation No.	8316
Attorney Docket No.	400.249US01

### INFORMATION DISCLOSURE STATEMENT FORM PTO-1449

Title: NROM MEMORY CELL, MEMORY ARRAY, RELATED DEVICES AND METHODS

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#### **SUPPLEMENTAL** INFORMATION DISCLOSURE **STATEMENT FORM PTO-1449**

Title: NROM MEMORY CELL, MEMORY ARRAY, RELATED DEVICES AND METHODS Sheet 1 of 1

Examiner Initials	Document No.	Issue/Publication Date	Name	Filing Date
1	5,617,351	04/01/1997	Bertin	06/05/1995
10	6,114,725	09/05/2000	Furukawa	06/09/1998

Examiner	Foreign Patent		Name	Publication	Translation
Initials	Country	No.		Date	

	Other References	
Examiner Initials	Author, Title, Date, Pages, etc.	

Examiner		Date	/.	/		
Signature	0 7	Considered /	140	U05		
*Examiner: Initial-if-citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not						